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EXAMINER INITIAL	DOCUMENT NUMBER	SENT SITE	NAME	CLASS SU	BCLASS THUNG DATE OF APPROPRIATE)
AP.	4,058,430	11/15/77 Sc	untola et al.		
K	5,711,811	01/27/98 Si	untola et al.		
		<del>                                     </del>			

EXAMINER INITIAL	OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)
A	Mölsä, Heini, et al., "Growth of Yttrium Oxide Thin Films from β-Diketonate Precursor," Adv. Materials for Optics and Electronics, 4: 389-400 (1994)
-10-1	Putkonen, Matti, et al., "Low-Temperature ALE Deposition of Y <sub>2</sub> O <sub>3</sub> Thin Films from β-Diketonate Precursors," Chem. Vap. Deposition, 7: 44-50 (2001)
	Hong, M., et al., "Epitaxial Cubic Gadalinium Oxide as a Dielectric for Gallium Arsenide Passivation," Science, 283:1897-1900 (1999)
	Seim, Helene, et al., "Growth of LaCoO3 thin films from β-Diketonate Precursors," Appl. Surf. Science, 112:243-250 (1997)
	Seim, Helene, et al., "Deposition of LaNiO3 thin films in an atomic layer epitaxy reactor," J. Mater. Chem., 7:449-454 (1997)
	Cho, MH, et al., "Growth stage of crystalline Y2O3 film on Si(100) grown by an ionized cluster beam deposition," J. Appl. Phys., 85:2909-2914 (1999)
	Kingon, Angus I., et al., "Alternative dielectrics to silicon dioxide for memory and logic devices," Nature, 406:1032-1038 (2000)
	Nieminen, Minna et al., *Formation and stability of lanthanum oxide think films deposited from β-diketonate precursor,* Appl. Surf. Science, 174:155-165 (2001)
	Gaboriaud, R.J. et al., "Microstructural investigations of Y2O3 thin films deposited by laser ablation on MgO," Appl. Phys. A., 71:675-680 (2000)
-	Ninistö, Laurie, "Advanced Thin Films For Electronics And Opto-Electronics By Atomic Layer Epilaxy," Int'l Semiconductor Conf., 23rd Ed., Vol. 1, pp. 33-42 (2000)
10	Suntola, Tuomo, "Atomic Layer Epitaxy," Handbook of Grystal Growth, Part B, Ch. 14, pp. 601-663
-1-36	
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DATE CONSIDERED EXAMINER

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